

IN THE SPECIFICATION:

Please replace the paragraph beginning at Page 1, line 29, and continuing at Page 2, lines 1 - 3, with the following paragraph, where underlined portions are being added and strike-through portions are being deleted.

- - One type of such lithography system is the variable axis immersion lens electron beam system, see, for example, U.S. Patent No. 4,544,846, to Langner et al. (herein "Langner et al."), incorporated by reference in its entirety. FIG. 2 and FIG. 4A of Langner et al. are reproduced respectively as FIG. 1A and FIG. 1B of the present disclosure. The Langner et al. Background section describes a variable axis electron beam projection system as being one where the electron optical axis of the projection system is shifted so as to be coincident with a deflected electron beam used to write on the target at all times. Shifting the electron optical axis is said to cause the electron beam to always land perpendicular to the target and to eliminate lens aberrations which are caused by off-axis electron beams . - -